

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	3586	((568/659) or (568/660) or (568/661) or (568/662) or (568/663) or (568/811) or (568/812) or (568/813) or (568/814) or (556/9) or (556/12)). CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/02/18 13:10
L2	1827283	copper or iron or cobalt or nickel or rhodium or palladium or ruthenium or platinum	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/18 13:10
L3	1443	I1 and I2	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/18 13:11
L4	56063	phosphine	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/18 13:11
L5	314	I3 and I4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/18 13:11
L6	206666	(sodium near2 carbonate) or (potassium near2 carbonate)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/18 13:12
L7	73	I5 and I6	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/18 13:30
L8	337878	styrene or vinylbenzene or phenylethylene or cinnamene	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/18 13:32
L9	351	I3 and I8	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/18 13:32

L10	335	I9 not I7	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/18 13:36
L11	55	I6 and I10	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/18 13:41
L12	27028	sumida.in. or kume.in. or koga.in. or komoriya.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/18 13:42
L13	341	I8 and I12	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/18 13:42

10/600,510

Connecting via Winsock to STN

Welcome to STN International! Enter x:x

LOGINID:SSSPTA1204RXW

PASSWORD:

TERMINAL (ENTER 1, 2, 3, OR ?):2

\* \* \* \* \* Welcome to STN International \* \* \* \* \*

NEWS	1		Web Page URLs for STN Seminar Schedule - N. America
NEWS	2		"Ask CAS" for self-help around the clock
NEWS	3	SEP 01	New pricing for the Save Answers for SciFinder Wizard within STN Express with Discover!
NEWS	4	OCT 28	KOREAPAT now available on STN
NEWS	5	NOV 30	PHAR reloaded with additional data
NEWS	6	DEC 01	LISA now available on STN
NEWS	7	DEC 09	12 databases to be removed from STN on December 31, 2004
NEWS	8	DEC 15	MEDLINE update schedule for December 2004
NEWS	9	DEC 17	ELCOM reloaded; updating to resume; current-awareness alerts (SDIs) affected
NEWS	10	DEC 17	COMPUAB reloaded; updating to resume; current-awareness alerts (SDIs) affected
NEWS	11	DEC 17	SOLIDSTATE reloaded; updating to resume; current-awareness alerts (SDIs) affected
NEWS	12	DEC 17	CERAB reloaded; updating to resume; current-awareness alerts (SDIs) affected
NEWS	13	DEC 17	THREE NEW FIELDS ADDED TO IFIPAT/IFIUDE/IFICDB
NEWS	14	DEC 30	EPFULL: New patent full text database to be available on STN
NEWS	15	DEC 30	CAPLUS - PATENT COVERAGE EXPANDED
NEWS	16	JAN 03	No connect-hour charges in EPFULL during January and February 2005
NEWS	17	JAN 26	CA/CAPLUS - Expanded patent coverage to include the Russian Agency for Patents and Trademarks (ROSPATENT)
NEWS	18	FEB 10	STN Patent Forums to be held in March 2005
NEWS	19	FEB 16	STN User Update to be held in conjunction with the 229th ACS National Meeting on March 13, 2005
NEWS EXPRESS			JANUARY 10 CURRENT WINDOWS VERSION IS V7.01a, CURRENT MACINTOSH VERSION IS V6.0c(ENG) AND V6.0Jc(JP), AND CURRENT DISCOVER FILE IS DATED 10 JANUARY 2005
NEWS HOURS			STN Operating Hours Plus Help Desk Availability
NEWS INTER			General Internet Information
NEWS LOGIN			Welcome Banner and News Items
NEWS PHONE			Direct Dial and Telecommunication Network Access to STN
NEWS WWW			CAS World Wide Web Site (general information)

Enter NEWS followed by the item number or name to see news on that specific topic.

All use of STN is subject to the provisions of the STN Customer agreement. Please note that this agreement limits use to scientific research. Use for software development or design or implementation of commercial gateways or other similar uses is prohibited and may result in loss of user privileges and other penalties.

10/600,510

\* \* \* \* \* STN Columbus \* \* \* \* \*

FILE 'HOME' ENTERED AT 14:07:10 ON 18 FEB 2005

=> FIL STNGUIDE

COST IN U.S. DOLLARS

SINCE FILE

TOTAL

ENTRY

SESSION

FULL ESTIMATED COST

0.21

0.21

FILE 'STNGUIDE' ENTERED AT 14:07:26 ON 18 FEB 2005

USE IS SUBJECT TO THE TERMS OF YOUR CUSTOMER AGREEMENT

COPYRIGHT (C) 2005 AMERICAN CHEMICAL SOCIETY, JAPAN SCIENCE

AND TECHNOLOGY CORPORATION, AND FACHINFORMATIONSZENTRUM KARLSRUHE

FILE CONTAINS CURRENT INFORMATION.

LAST RELOADED: Feb 11, 2005 (20050211/UP).

=> file reg

COST IN U.S. DOLLARS

SINCE FILE

TOTAL

ENTRY

SESSION

FULL ESTIMATED COST

0.06

0.27

FILE 'REGISTRY' ENTERED AT 14:07:46 ON 18 FEB 2005

USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.

PLEASE SEE "HELP USAGETERMS" FOR DETAILS.

COPYRIGHT (C) 2005 American Chemical Society (ACS)

Property values tagged with IC are from the ZIC/VINITI data file provided by InfoChem.

STRUCTURE FILE UPDATES: 16 FEB 2005 HIGHEST RN 832673-31-1

DICTIONARY FILE UPDATES: 16 FEB 2005 HIGHEST RN 832673-31-1

TSCA INFORMATION NOW CURRENT THROUGH JANUARY 18, 2005

Please note that search-term pricing does apply when conducting SmartSELECT searches.

Crossover limits have been increased. See HELP CROSSOVER for details.

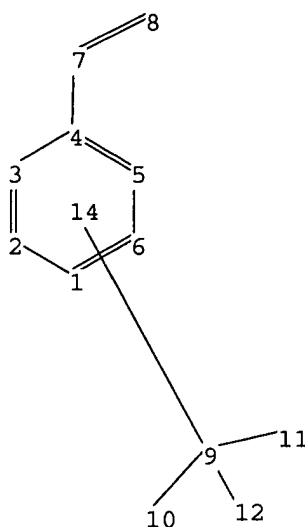
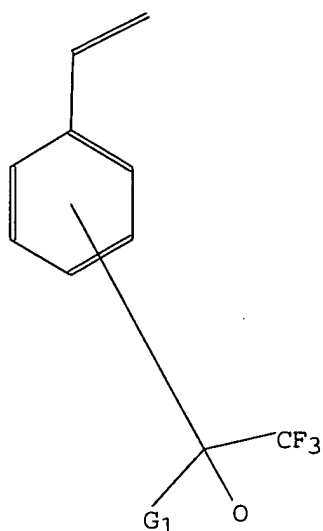
Experimental and calculated property data are now available. For more information enter HELP PROP at an arrow prompt in the file or refer to the file summary sheet on the web at:

<http://www.cas.org/ONLINE/DBSS/registryss.html>

=>

Uploading C:\Program Files\Stnexp\Queries\10600510.str

10/600,510



chain nodes :  
7 8 9 10 11 12  
ring nodes :  
1 2 3 4 5 6  
chain bonds :  
4-7 7-8 9-12 9-10 9-11  
ring bonds :  
1-2 1-6 2-3 3-4 4-5 5-6  
exact/norm bonds :  
9-12 9-10  
exact bonds :  
4-7 7-8 9-11  
normalized bonds :  
1-2 1-6 2-3 3-4 4-5 5-6  
isolated ring systems :  
containing 1 :

G1:CH<sub>3</sub>,CF<sub>3</sub>

Match level :

1:Atom 2:Atom 3:Atom 4:Atom 5:Atom 6:Atom 7:CLASS 8:CLASS 9:CLASS 10:CLASS  
11:CLASS 12:CLASS 14:CLASS

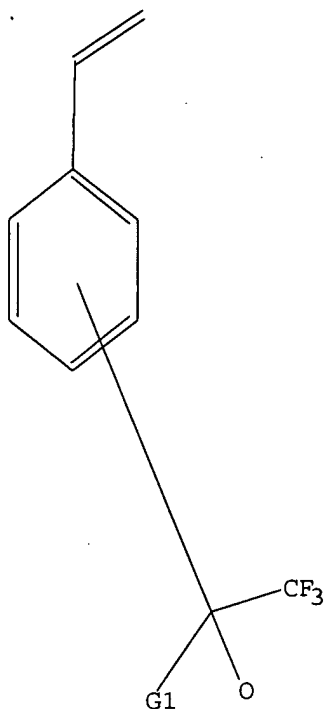
L1 STRUCTURE UPLOADED

=> d

L1 HAS NO ANSWERS

L1 STR

10/600,510



G1 Me,CF3

Structure attributes must be viewed using STN Express query preparation.

=> s l1

SAMPLE SEARCH INITIATED 14:08:23 FILE 'REGISTRY'  
SAMPLE SCREEN SEARCH COMPLETED - 1297 TO ITERATE

77.1% PROCESSED 1000 ITERATIONS  
INCOMPLETE SEARCH (SYSTEM LIMIT EXCEEDED)  
SEARCH TIME: 00.00.01

29 ANSWERS

FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\*  
BATCH \*\*COMPLETE\*\*  
PROJECTED ITERATIONS: 23780 TO 28100  
PROJECTED ANSWERS: 385 TO 1119

L2 29 SEA SSS SAM L1

=> s l1 ful

FULL SEARCH INITIATED 14:08:52 FILE 'REGISTRY'  
FULL SCREEN SEARCH COMPLETED - 26059 TO ITERATE

100.0% PROCESSED 26059 ITERATIONS  
SEARCH TIME: 00.00.01

669 ANSWERS

L3 669 SEA SSS FUL L1

=> d scan

L3 669 ANSWERS REGISTRY COPYRIGHT 2005 ACS on STN  
IN Carbonic acid, 1,1-dimethylethyl 1-[4-ethenyl-2-(trifluoromethyl)phenyl]-  
2,2,2-trifluoro-1-(trifluoromethyl)ethyl ester, polymer with

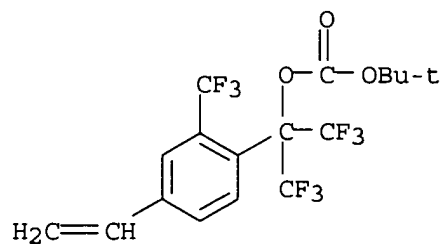
10/600,510

1-(1,1-dimethylethoxy)-4-ethenylbenzene and 4-ethenyl- $\alpha,\alpha$ -bis(trifluoromethyl)benzenemethanol (9CI)

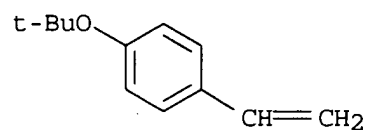
MF (C17 H15 F9 O3 . C12 H16 O . C11 H8 F6 O)x

CI PMS

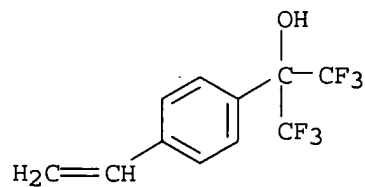
CM 1



CM 2



CM 3



HOW MANY MORE ANSWERS DO YOU WISH TO SCAN? (1):0

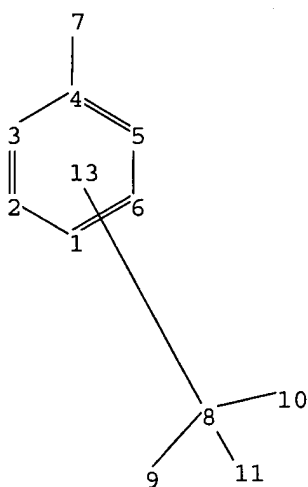
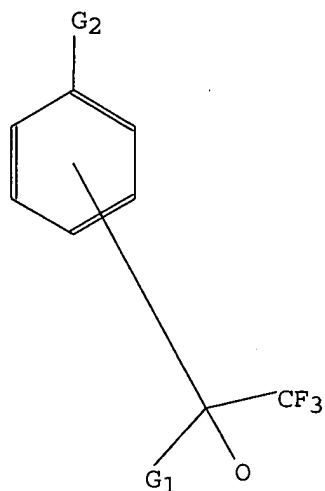
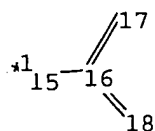
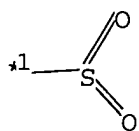
=> ....Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=>

Uploading C:\Program Files\Stnexp\Queries\10600510a.str

10/600,510



chain nodes :  
7 8 9 10 11 15 16 17 18  
ring nodes :  
1 2 3 4 5 6  
chain bonds :  
4-7 8-11 8-9 8-10 15-16 16-17 16-18  
ring bonds :  
1-2 1-6 2-3 3-4 4-5 5-6  
exact/norm bonds :  
4-7 8-11 8-9 15-16 16-17 16-18  
exact bonds :  
8-10  
normalized bonds :  
1-2 1-6 2-3 3-4 4-5 5-6  
isolated ring systems :  
containing 1 :

G1:CH3,CF3

G2:X, [\*1]

Match level :

1:Atom 2:Atom 3:Atom 4:Atom 5:Atom 6:Atom 7:CLASS 8:CLASS 9:CLASS 10:CLASS  
11:CLASS 13:CLASS 15:CLASS 16:CLASS 17:CLASS 18:CLASS

L4 STRUCTURE UPLOADED

=> que L4



10/600,510

L5 QUE L4

=> d

L5 HAS NO ANSWERS

L4 STR

\* STRUCTURE DIAGRAM TOO LARGE FOR DISPLAY - AVAILABLE VIA OFFLINE PRINT \*

Structure attributes must be viewed using STN Express query preparation.

L5 QUE L4

=> s 15

SAMPLE SEARCH INITIATED 14:10:16 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 542 TO ITERATE

100.0% PROCESSED 542 ITERATIONS

23 ANSWERS

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\*

BATCH \*\*COMPLETE\*\*

PROJECTED ITERATIONS: 9444 TO 12236

PROJECTED ANSWERS: 172 TO 746

L6 23 SEA SSS SAM L4

=> s 15 ful

FULL SEARCH INITIATED 14:10:22 FILE 'REGISTRY'

FULL SCREEN SEARCH COMPLETED - 10993 TO ITERATE

100.0% PROCESSED 10993 ITERATIONS

345 ANSWERS

SEARCH TIME: 00.00.01

L7 345 SEA SSS FUL L4

=> file caplus

COST IN U.S. DOLLARS

SINCE FILE

TOTAL

ENTRY

SESSION

FULL ESTIMATED COST

323.95

324.22

FILE 'CAPLUS' ENTERED AT 14:10:45 ON 18 FEB 2005

USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.

PLEASE SEE "HELP USAGETERMS" FOR DETAILS.

COPYRIGHT (C) 2005 AMERICAN CHEMICAL SOCIETY (ACS)

Copyright of the articles to which records in this database refer is held by the publishers listed in the PUBLISHER (PB) field (available for records published or updated in Chemical Abstracts after December 26, 1996), unless otherwise indicated in the original publications. The CA Lexicon is the copyrighted intellectual property of the American Chemical Society and is provided to assist you in searching databases on STN. Any dissemination, distribution, copying, or storing of this information, without the prior written consent of CAS, is strictly prohibited.

FILE COVERS 1907 - 18 Feb 2005 VOL 142 ISS 9

FILE LAST UPDATED: 17 Feb 2005 (20050217/ED)

This file contains CAS Registry Numbers for easy and accurate substance identification.

10/600,510

=> s 13 and 17

.255 L3

170 L7

L8 12 L3 AND L7

=> dup rem 18

PROCESSING COMPLETED FOR L8

L9 12 DUP REM L8 (0 DUPLICATES REMOVED)

=> d 1-12 ti

L9 ANSWER 1 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

TI Process for producing fluorine-containing, polymerizable styrene monomer and intermediates used in same

L9 ANSWER 2 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

TI Photosensitive resin composition

L9 ANSWER 3 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

TI Photosensitive resin composition

L9 ANSWER 4 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

TI Photosensitive resin composition for photolithography

L9 ANSWER 5 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

TI Positive-working photoresist composition containing fluoro-substituted nitrogen compound

L9 ANSWER 6 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

TI Vacuum UV-sensitive resin composition containing ionic compound reactive towards acid

L9 ANSWER 7 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

TI Positive-working vacuum UV-sensitive photoresist material composition containing specific resin

L9 ANSWER 8 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

TI Positive-working resist composition containing specific fluorine group-containing resin

L9 ANSWER 9 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

TI Positive resist composition

L9 ANSWER 10 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

TI Polymers with fluorinated styrene-based mer units, their positive resist materials, and their patterning

L9 ANSWER 11 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

TI Sulfonic acid esters, their production and photosensitive compositions containing them.

L9 ANSWER 12 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

TI The synthesis and attempted polymerization of an  $\alpha,\beta,\beta$ -trifluorostyrene disubstituted by hexafluoro-2-propyl groups

=> d 1-12 bib fhitr

L9 ANSWER 1 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2004:3703 CAPLUS

DN 140:60144

10/600,510

TI Process for producing fluorine-containing, polymerizable styrene monomer  
and intermediates used in same  
IN Sumida, Shinichi; Kume, Takashi; Koga, Sunao; Komoriya, Haruhiko  
PA Central Glass Company, Limited, Japan  
SO U.S. Pat. Appl. Publ., 16 pp.

CODEN: USXXCO

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 2004002612	A1	20040101	US 2003-600510	20030623
	JP 2004026691	A2	20040129	JP 2002-183138	20020624
PRAI	JP 2002-183138	A	20020624		

OS MARPAT 140:60144

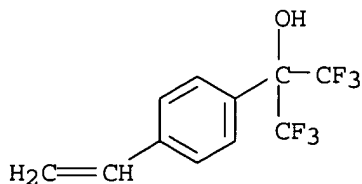
IT **2386-82-5P**

RL: IMF (Industrial manufacture); PREP (Preparation)

(monomer; preparation of fluorine-containing polymerizable styrene monomers)

RN 2386-82-5 CAPLUS

CN Benzenemethanol, 4-ethenyl- $\alpha,\alpha$ -bis(trifluoromethyl)- (9CI)  
(CA INDEX NAME)



L9 ANSWER 2 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2004:1012045 CAPLUS

DN 142:13671

TI Photosensitive resin composition

IN Kanna, Shinichi; Mizutani, Kazuyoshi; Sasaki, Tomoya

PA Fuji Photo Film Co., Ltd., Japan

SO Eur. Pat. Appl., 133 pp.

CODEN: EPXXDW

DT Patent

LA English

FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1480079	A2	20041124	EP 2004-19923	20030606
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK				
	JP 2004012898	A2	20040115	JP 2002-167393	20020607
	JP 2004029111	A2	20040129	JP 2002-181384	20020621
	JP 2004029136	A2	20040129	JP 2002-181588	20020621
	EP 1376232	A1	20040102	EP 2003-12226	20030606
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK				
PRAI	JP 2002-167393	A	20020607		
	JP 2002-181384	A	20020621		
	JP 2002-181588	A	20020621		
	EP 2003-12226	A3	20030606		

IT **485390-42-9P**

RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

10/600,510

(photosensitive resin composition)

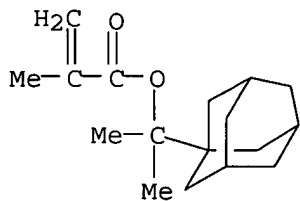
RN 485390-42-9 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-methyl-1-tricyclo[3.3.1.1<sup>3,7</sup>]dec-1-ylethyl ester, polymer with 4-ethenyl- $\alpha,\alpha$ -bis(trifluoromethyl)benzenemethanol and 1-ethenyl-4-(1-methoxyethoxy)benzene (9CI) (CA INDEX NAME)

CM 1

CRN 279218-76-7

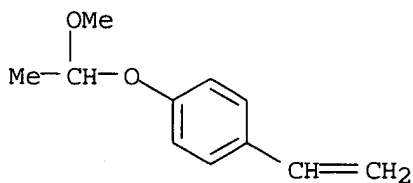
CMF C17 H26 O2



CM 2

CRN 151189-10-5

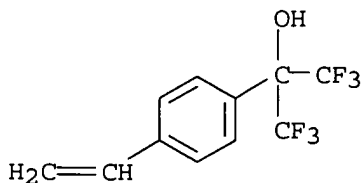
CMF C11 H14 O2



CM 3

CRN 2386-82-5

CMF C11 H8 F6 O



L9 ANSWER 3 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2004:5239 CAPLUS

DN 140:67635

TI Photosensitive resin composition

IN Kanna, Shinichi; Mizutani, Kazuyoshi; Sasaki, Tomoya

PA Fuji Photo Film Co., Ltd., Japan

SO Eur. Pat. Appl., 136 pp.

CODEN: EPXXDW

10/600,510

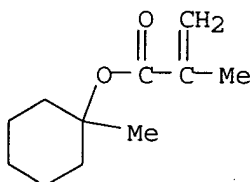
DT Patent  
LA English  
FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1376232	A1	20040102	EP 2003-12226	20030606
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK				
	JP 2004012898	A2	20040115	JP 2002-167393	20020607
	JP 2004029111	A2	20040129	JP 2002-181384	20020621
	JP 2004029136	A2	20040129	JP 2002-181588	20020621
	US 2004009430	A1	20040115	US 2003-455459	20030606
	EP 1480079	A2	20041124	EP 2004-19923	20030606
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK				
PRAI	JP 2002-167393	A	20020607		
	JP 2002-181384	A	20020621		
	JP 2002-181588	A	20020621		
	EP 2003-12226	A3	20030606		
IT	<b>485390-41-8P</b>				
	RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (microlithog. photosensitive resin composition containing)				
RN	485390-41-8 CAPLUS				
CN	2-Propenoic acid, 2-methyl-, 1-methylcyclohexyl ester, polymer with 4-ethenyl- $\alpha,\alpha$ -bis(trifluoromethyl)benzenemethanol and 2-(4-ethenylphenoxy)tetrahydro-2H-pyran (9CI) (CA INDEX NAME)				

CM 1

CRN 76392-14-8

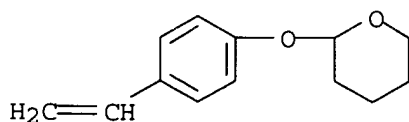
CMF C11 H18 O2



CM 2

CRN 65409-15-6

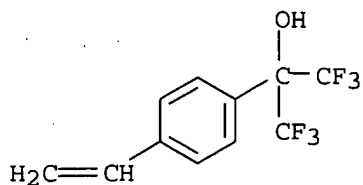
CMF C13 H16 O2



CM 3

CRN 2386-82-5

CMF C11 H8 F6 O



RE.CNT 5 THERE ARE 5 CITED REFERENCES AVAILABLE FOR THIS RECORD  
ALL CITATIONS AVAILABLE IN THE RE FORMAT

L9 ANSWER 4 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN  
AN 2003:945845 CAPLUS  
DN 140:21261  
TI Photosensitive resin composition for photolithography  
IN Kanna, Shinichi; Mizutani, Kazuyoshi; Sasaki, Tomoya  
PA Fuji Photo Film Co., Ltd., Japan  
SO Jpn. Kokai Tokkyo Koho, 71 pp.  
CODEN: JKXXAF

DT Patent  
LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2003344994	A2	20031203	JP 2002-154391	20020528
PRAI	JP 2002-154391		20020528		

IT **430437-18-6P**

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(photoresist composition containing acid-decomposable polymer, acid generator, and F-containing solvent)

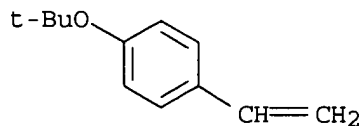
RN 430437-18-6 CAPLUS

CN Benzenemethanol, 4-ethenyl- $\alpha,\alpha$ -bis(trifluoromethyl)-, polymer with 1-(1,1-dimethylethoxy)-4-ethenylbenzene (9CI) (CA INDEX NAME)

CM 1

CRN 95418-58-9

CMF C12 H16 O

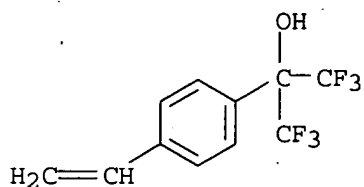


CM 2

CRN 2386-82-5

CMF C11 H8 F6 O

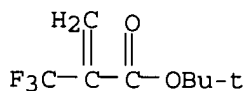
10/600,510



L9 ANSWER 5 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN  
AN 2003:369197 CAPLUS  
DN 138:393073  
TI Positive-working photoresist composition containing fluoro-substituted  
nitrogen compound  
IN Fujimori, Toru; Kanna, Shinichi  
PA Fuji Photo Film Co., Ltd., Japan  
SO Jpn. Kokai Tokkyo Koho, 53 pp.  
CODEN: JKXXAF  
DT Patent  
LA Japanese  
FAN.CNT 1

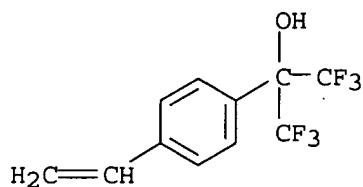
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2003140349	A2	20030514	JP 2001-339439	20011105
PRAI	JP 2001-339439		20011105		
IT	370866-13-0P				

RL: PNU (Preparation, unclassified); TEM (Technical or engineered material  
use); PREP (Preparation); USES (Uses)  
(pos. photoresist containing F-containing alkali-soluble polymer, acid  
generator,  
and F-containing nitrogen compound)  
RN 370866-13-0 CAPLUS  
CN 2-Propenoic acid, 2-(trifluoromethyl)-, 1,1-dimethylethyl ester, polymer  
with 4-ethenyl- $\alpha,\alpha$ -bis(trifluoromethyl)benzenemethanol (9CI)  
(CA INDEX NAME)  
CM 1  
CRN 105935-24-8  
CMF C8 H11 F3 O2



CM 2  
CRN 2386-82-5  
CMF C11 H8 F6 O

10/600,510



L9 ANSWER 6 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN  
AN 2003:152372 CAPLUS  
DN 138:212786  
TI Vacuum UV-sensitive resin composition containing ionic compound reactive  
towards acid  
IN Kanna, Shinichi; Mizutani, Kazuyoshi  
PA Fuji Photo Film Co., Ltd., Japan  
SO Jpn. Kokai Tokkyo Koho, 66 pp.  
CODEN: JKXXAF

DT Patent  
LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2003057826	A2	20030228	JP 2001-250535	20010821
PRAI	JP 2001-250535		20010821		

IT 485390-41-8P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material  
use); PREP (Preparation); USES (Uses)

(resin; Vacuum UV-sensitive resin composition containing ionic compound  
reactive towards acid)

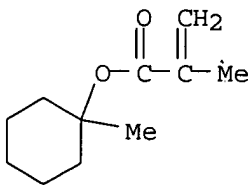
RN 485390-41-8 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-methylcyclohexyl ester, polymer with  
4-ethenyl- $\alpha,\alpha$ -bis(trifluoromethyl)benzenemethanol and  
2-(4-ethenylphenoxy)tetrahydro-2H-pyran (9CI) (CA INDEX NAME)

CM 1

CRN 76392-14-8

CMF C11 H18 O2



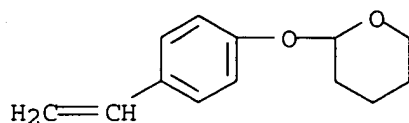
CM 2

CRN 65409-15-6

CMF C13 H16 O2



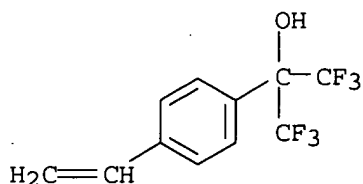
10/600,510



CM 3

CRN 2386-82-5

CMF C11 H8 F6 O



L9 ANSWER 7 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2003:35187 CAPLUS

DN 138:98199

TI Positive-working vacuum UV-sensitive photoresist material composition containing specific resin

IN Kanna, Shinichi; Mizutani, Kazuyoshi

PA Fuji Photo Film Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 39 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2003015298	A2	20030115	JP 2001-202241	20010703
PRAI	JP 2001-202241		20010703		

IT **485390-41-8P**

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(resin; pos.-working vacuum UV-sensitive photoresist material composition containing specific resin)

RN 485390-41-8 CAPLUS

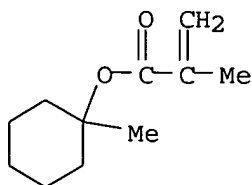
CN 2-Propenoic acid, 2-methyl-, 1-methylcyclohexyl ester, polymer with 4-ethenyl- $\alpha,\alpha$ -bis(trifluoromethyl)benzenemethanol and 2-(4-ethenylphenoxy)tetrahydro-2H-pyran (9CI) (CA INDEX NAME)

CM 1

CRN 76392-14-8

CMF C11 H18 O2

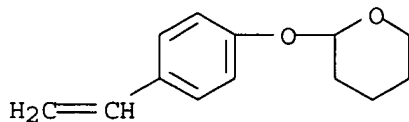
10/600,510



CM 2

CRN 65409-15-6

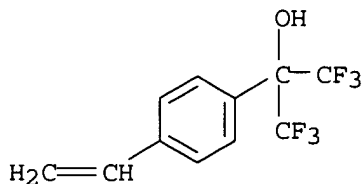
CMF C13 H16 O2



CM 3

CRN 2386-82-5

CMF C11 H8 F6 O



L9 ANSWER 8 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2003:470377 CAPLUS

DN 139:44224

TI Positive-working resist composition containing specific fluorine group-containing resin

IN Kanna, Shinichi; Mizutani, Kazuyoshi; Kodama, Kunihiro; Sasaki, Tomoya

PA Fuji Photo Film Co., Ltd., Japan

SO Eur. Pat. Appl., 80 pp.

CODEN: EPXXDW

DT Patent

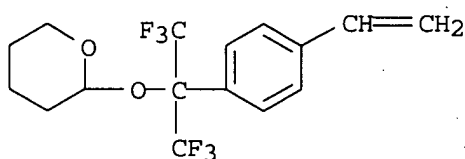
LA English

FAN.CNT 1

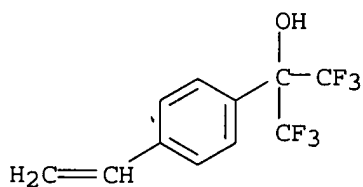
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1319981	A2	20030618	EP 2002-27667	20021212
	EP 1319981	A3	20030723		
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, SK				
	US 2003194650	A1	20031016	US 2002-317110	20021212
	JP 2003241386	A2	20030827	JP 2002-362629	20021213
PRAI	JP 2001-380104	A	20011213		

10/600,510

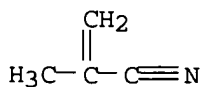
JP 2001-380105      A      20011213  
IT    **430437-03-9P**  
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
     (fluorine group-containing resin)  
RN    430437-03-9    CAPLUS  
CN    2-Propenenitrile, 2-methyl-, polymer with 4-ethenyl- $\alpha,\alpha$ -bis(trifluoromethyl)benzenemethanol and 2-[1-(4-ethenylphenyl)-2,2,2-trifluoro-1-(trifluoromethyl)ethoxy]tetrahydro-2H-pyran (9CI) (CA INDEX NAME)  
  
CM    1  
  
CRN   430437-02-8  
CMF   C16 H16 F6 O2



CM    2  
  
CRN   2386-82-5  
CMF   C11 H8 F6 O



CM    3  
  
CRN   126-98-7  
CMF   C4 H5 N



L9    ANSWER 9 OF 12    CAPLUS    COPYRIGHT 2005 ACS on STN  
AN    2002:392162    CAPLUS  
DN    136:409022  
TI    Positive resist composition  
IN    Aoai, Toshiaki; Yasunami, Shoichiro; Mizutani, Kazuyoshi; Kanna, Shinichi  
PA    Fuji Photo Film Co., Ltd., Japan  
SO    U.S. Pat. Appl. Publ., 56 pp.  
     CODEN: USXXCO

10/600,510

DT Patent  
LA English  
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 2002061464	A1	20020523	US 2001-961281	20010925
	US 6852467	B2	20050208		
	JP 2002333715	A2	20021122	JP 2001-202298	20010703
	TW 528931	B	20030421	TW 2001-90123599	20010925
PRAI	JP 2000-292537	A	20000926		
	JP 2000-379284	A	20001213		
	JP 2001-62158	A	20010306		
	JP 2001-202298	A	20010703		

IT **430437-01-7P**

RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
(fluorine group-containing resin for pos. resist composition)

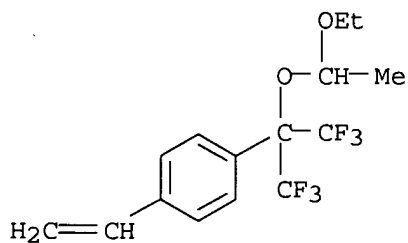
RN 430437-01-7 CAPLUS

CN 2-Propenenitrile, 2-methyl-, polymer with 4-ethenyl- $\alpha,\alpha$ -bis(trifluoromethyl)benzenemethanol and 1-ethenyl-4-[1-(1-ethoxyethoxy)-2,2,2-trifluoro-1-(trifluoromethyl)ethyl]benzene (9CI) (CA INDEX NAME)

CM 1

CRN 430437-00-6

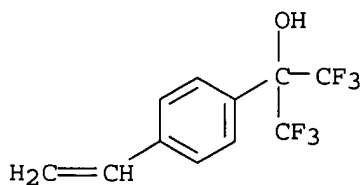
CMF C15 H16 F6 O2



CM 2

CRN 2386-82-5

CMF C11 H8 F6 O

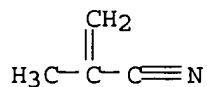


CM 3

CRN 126-98-7

CMF C4 H5 N

10/600,510



L9 ANSWER 10 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2002:847803 CAPLUS

DN 137:360305

TI Polymers with fluorinated styrene-based mer units, their positive resist materials, and their patterning

IN Hatakeyama, Jun; Harada, Yuji; Watanabe, Atsushi; Sasako, Masaru; Endo, Masataka; Kishimura, Shinji; Otani, Mitsutaka; Miyazawa, Satoru; Tsutsumi, Kentaro; Maeda, Kazuhiko

PA Shin-Etsu Chemical Industry Co., Ltd., Japan; Matsushita Electric Industrial Co., Ltd.; Central Glass Co., Ltd.

SO Jpn. Kokai Tokkyo Koho, 28 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN. CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2002322217	A2	20021108	JP 2001-128529	20010426
PRAI	JP 2001-128529		20010426		

IT **474088-23-8P**

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(polymers with fluorinated styrene-based mer units, their pos. DUV resist materials, and their patterning)

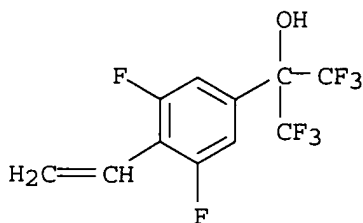
RN 474088-23-8 CAPLUS

CN 2-Propenoic acid, 1,1-dimethylethyl ester, polymer with 4-ethenyl-3,5-difluoro- $\alpha,\alpha$ -bis(trifluoromethyl)benzenemethanol (9CI) (CA INDEX NAME)

CM 1

CRN 474088-22-7

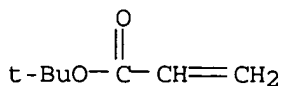
CMF C11 H6 F8 O



CM 2

CRN 1663-39-4

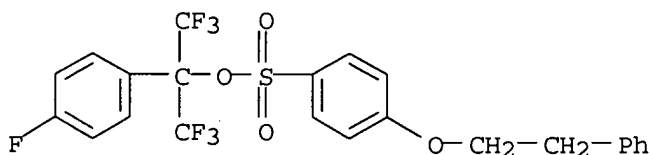
CMF C7 H12 O2



10/600,510

L9 ANSWER 11 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN  
AN 1995:441113 CAPLUS  
DN 122:201235  
TI Sulfonic acid esters, their production and photosensitive compositions containing them.  
IN Pawlowski, Georg; Spiess, Walter; Roeschert, Horst; Appel, Wolfgang; Herr, Walter  
PA Hoechst A.-G., Germany  
SO Ger. Offen., 26 pp.  
CODEN: GWXXBX  
DT Patent  
LA German  
FAN. CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 4302681	A1	19940804	DE 1993-4302681	19930201
	WO 9418606	A1	19940818	WO 1993-EP2701	19931004
	W: JP, KR, US				
	RW: AT, BE, CH, DE, DK, ES, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE				
	EP 681713	A1	19951115	EP 1993-921907	19931004
	EP 681713	B1	19981118		
	R: DE, FR, GB, IT				
	JP 08506908	T2	19960723	JP 1993-510420	19931004
	JP 3348789	B2	20021120	JP 1994-510420	19931004
	US 5716756	A	19980210	US 1995-424532	19950530
PRAI	DE 1993-4302681	A	19930201		
	WO 1993-EP2701	W	19931004		
OS	MARPAT 122:201235				
IT	161759-14-4				
	RL: MOA (Modifier or additive use); USES (Uses)				
	(photoacid generator)				
RN	161759-14-4 CAPLUS				
CN	Benzenesulfonic acid, 4-(2-phenylethoxy)-, 2,2,2-trifluoro-1-(4-fluorophenyl)-1-(trifluoromethyl)ethyl ester (9CI) (CA INDEX NAME)				

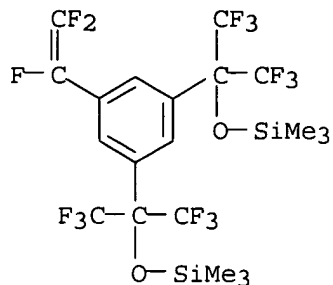


L9 ANSWER 12 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN  
AN 1991:558597 CAPLUS  
DN 115:158597  
TI The synthesis and attempted polymerization of an  $\alpha,\beta,\beta$ -trifluorostyrene disubstituted by hexafluoro-2-propyl groups  
AU Sprague, Lee G.; Snow, Arthur W.; Griffith, James R.  
CS Chem. Div., Nav. Res. Lab., Washington, DC, 20375-5000, USA  
SO Journal of Fluorine Chemistry (1991), 52(3), 301-6  
CODEN: JFLCAR; ISSN: 0022-1139  
DT Journal  
LA English  
OS CASREACT 115:158597  
IT 136365-60-1P  
RL: SPN (Synthetic preparation); PREP (Preparation)  
(preparation and attempted polymerization of)

10/600,510

RN 136365-60-1 CAPLUS

CN Silane, [[5-(trifluoroethenyl)-1,3-phenylene]bis[[2,2,2-trifluoro-1-(trifluoromethyl)ethylidene]oxy]]bis[trimethyl- (9CI) (CA INDEX NAME)



=> log hold

COST IN U.S. DOLLARS

SINCE FILE	TOTAL
ENTRY	SESSION
48.57	372.79

FULL ESTIMATED COST

SESSION WILL BE HELD FOR 60 MINUTES

STN INTERNATIONAL SESSION SUSPENDED AT 14:15:59 ON 18 FEB 2005

Connecting via Winsock to STN

Welcome to STN International! Enter x:x

LOGINID:SSSPTA1204RXW

PASSWORD:

\*\*\*\*\* RECONNECTED TO STN INTERNATIONAL \*\*\*\*\*  
SESSION RESUMED IN FILE 'CAPLUS' AT 14:31:44 ON 18 FEB 2005  
FILE 'CAPLUS' ENTERED AT 14:31:44 ON 18 FEB 2005  
COPYRIGHT (C) 2005 AMERICAN CHEMICAL SOCIETY (ACS)

COST IN U.S. DOLLARS

SINCE FILE	TOTAL
ENTRY	SESSION
48.57	372.79

FULL ESTIMATED COST

=> D HIS

(FILE 'HOME' ENTERED AT 14:07:10 ON 18 FEB 2005)

FILE 'STNGUIDE' ENTERED AT 14:07:26 ON 18 FEB 2005

FILE 'REGISTRY' ENTERED AT 14:07:46 ON 18 FEB 2005

L1 STRUCTURE UPLOADED  
L2 29 S L1  
L3 669 S L1 FUL  
L4 STRUCTURE UPLOADED  
L5 QUE L4  
L6 23 S L5  
L7 345 S L5 FUL

FILE 'CAPLUS' ENTERED AT 14:10:45 ON 18 FEB 2005

10/600,510

L8 12 S L3 AND L7  
L9 12 DUP REM L8 (0 DUPLICATES REMOVED)

=> s l3/prep  
255 L3  
3264165 PREP/RL  
L10 131 L3/PREP  
(L3 (L) PREP/RL)

=> file save  
'SAVE' IS NOT A VALID FILE NAME  
SESSION CONTINUES IN FILE 'CAPLUS'  
Enter "HELP FILE NAMES" at an arrow prompt (=>) for a list of files that are available. If you have requested multiple files, you can specify a corrected file name or you can enter "IGNORE" to continue accessing the remaining file names entered.

=> save  
ENTER L#, L# RANGE, ALL, OR (END):l1-l10  
ENTER NAME OR (END):styrene  
STYRENE IS NOT A VALID SAVED NAME  
Enter the name you wish to use for the saved query, answer set, or L-number list. The name must:

1. Begin with a letter,
2. Have 1-12 characters,
3. Contain only letters (A-Z) and numbers (0-9),
4. End with /Q for a query (search profile, structure, or screen set), /A for an answer set, or /L for an L-number list.
5. Not already be in use as a saved name,
6. Not be END, SAV, SAVE, SAVED
7. Not have the form of an L-number (Lnnn).

ENTER NAME OR (END):styrene/a  
L1-L10 IS NOT ALLOWED WITH ANSWER SET NAME: STYRENE/A  
Selectively saving L-numbers to an L-number list can only be saved to a name ending with /L.

=> styrene/l  
STYRENE IS NOT A RECOGNIZED COMMAND  
The previous command name entered was not recognized by the system.  
For a list of commands available to you in the current file, enter "HELP COMMANDS" at an arrow prompt (=>).

=> help commands  
Enter one of these commands at the arrow prompt (=>).

ACTIVATE ----- Assign L#s to saved query or answer set.  
ANALYZE ----- Build expand terms from answer fields.  
ARCHIVE ----- Purchase rights for archiving.  
DELETE ----- Delete saved or current session items.  
DISPLAY ----- Display saved or current session items.  
DUPLICATE ---- Determine duplicate answers  
EDIT ----- Modify the text of an E-number entry.  
EXPAND ----- Look at the index around a term.  
FILE ----- Specify the search and display file.  
FOCUS ----- Rank answers in order of relevancy.  
FSEARCH ----- Find records from given patent family(s)  
FSORT ----- Sort patent records by patent family  
HELP ----- For help on how to use the system.  
INDEX ----- Specify the Index environment.  
LOGOFF ----- End the online session.  
NEWS ----- Display current news about the system.



10/600,510

ORDER ----- Order an original document or copy.  
PRINT ----- Print answers offline.  
QUERY ----- Define a search question (query).  
REDISTRIBUTE - Purchase rights for redistribution.  
SAVE ----- Save an L-numbered query or answer set.  
SDI ----- Request searches be run on file updates.  
SEARCH ----- Perform a search.  
SELECT ----- Build expand terms from answer fields.  
SET ----- Set terminal and interaction options.  
SORT ----- Sort Answers of an L-number list  
TABULATE ----- Analyze SmartSELECT L-number data.  
TRANSFER ----- Extract terms from answers and search.  
? ----- The same as HELP.  
Enter one of these commands at the arrow prompt (=>).

For more detailed information about a command, enter HELP followed by the command name at an arrow prompt.

Example: => HELP SEARCH

For information on entering multiple commands at a single arrow prompt, enter HELP COMMAND STACKING.

=> save l10  
ENTER NAME OR (END):styrene/a  
ANSWER SET L10 HAS BEEN SAVED AS 'STYRENE/A'

=> log y

COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	54.51	378.73

STN INTERNATIONAL LOGOFF AT 14:36:52 ON 18 FEB 2005

Connecting via Winsock to STN

Welcome to STN International! Enter x:x

LOGINID:SSSPTA1204RXW

PASSWORD:  
TERMINAL (ENTER 1, 2, 3, OR ?):2

\* \* \* \* \* Welcome to STN International \* \* \* \* \*

NEWS	1	Web Page URLs for STN Seminar Schedule - N. America
NEWS	2	"Ask CAS" for self-help around the clock
NEWS	3 SEP 01	New pricing for the Save Answers for SciFinder Wizard within STN Express with Discover!
NEWS	4 OCT 28	KOREAPAT now available on STN
NEWS	5 NOV 30	PHAR reloaded with additional data
NEWS	6 DEC 01	LISA now available on STN
NEWS	7 DEC 09	12 databases to be removed from STN on December 31, 2004
NEWS	8 DEC 15	MEDLINE update schedule for December 2004
NEWS	9 DEC 17	ELCOM reloaded; updating to resume; current-awareness